

SEPP17.001AUS



PATENT

#3B
JL
5.14.02

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant	:	NIINISTÖ et al.	Group Art Unit: 1762
Appl. No.	:	10/067,634)
Filed	:	February 4, 2002)
For	:	METHOD OF DEPOSITING RARE EARTH OXIDE THIN FILMS)
Examiner	:	Unknown)

COPY OF PAPERS
ORIGINALLY FILED

SECOND PRELIMINARY AMENDMENT

UNITED STATES PATENT AND TRADEMARK OFFICE
P.O. Box 2327
Arlington, VA 22202

Dear Sir:

Prior to examination on the merits, please amend the above-identified application as follows.

In the Specification:

Please insert the following paragraph on page 1, following the title:

B1
The present application claims priority to Japanese patent application number 2001-236874, filed August 3, 2001.

In the Claims: ✓ ✓

Please cancel Claims 1-14 and add the following new claims:

B2
15. (New) An atomic layer deposition (ALD) process for depositing rare earth metal oxide thin films on a substrate in a reaction space, comprising the steps of: